

ABSTRACT

The present invention provides a method of manufacturing a thin film magnetic head, capable of easily manufacturing a thin film magnetic head with high precision, in which a magnetic shield layer is disposed so as to surround a magnetic pole layer from three directions of a medium outflow direction and two side directions. In a magnetic pole formation region surrounded by a first gap layer portion, a magnetic pole layer and a second gap layer portion are formed and the magnetic pole layer is covered with the first and second gap layer portions. After that, a write shield layer is formed on the first and second gap layer portions so as to surround the magnetic pole layer from three directions (a trailing direction and two side directions). Since a gap between the magnetic layer and the write shield layer exerting an influence on recording characteristics is specified on the basis of the thickness of the first gap layer portion, different from the case where the gap is specified on the basis of pattern precision of the photolithography technique, the gap is controlled with high precision.